

## **IMPORTANT TOPICS**

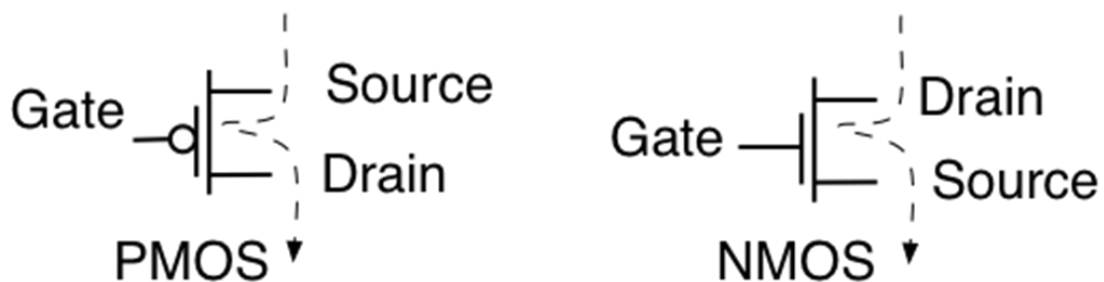
- Introduction to CMOS scaling
- It's History
- It's Application
- It's Working
- It's limitation
- Fin-FET {application ,working, adv and dis-adv, compare with CMOS}
- Technology mode {180nm, 90nm, ...}
- Difference b/w long and short channel
- LT spice software
- Spice Modelling

# INTRODUCTION TO CMOS

❖ CMOS (Complementary Metal-Oxide-Semiconductor) technology has been the backbone of the semiconductor industry.

❖ It behaves as logic gate.

❖ Its components are pmos & nmos.



❖ In pmos when  $\text{Gate} = 0\text{V}$ , then pmos will short circuit, act as ON, while when  $\text{Gate} = 1\text{V}$ , then pmos will open circuit, act as OFF.

❖ In nmos when  $\text{Gate} = 0\text{V}$ , then nmos will open circuit, act as OFF, while when  $\text{Gate} = 1\text{V}$ , then nmos will short circuit, act as ON.

# CMOS SCALING

❖ Defines as **reduction of the dimension** of different **parameters** of MOSFET.

❖ Why Scaling ???

- 1) Increase device packing density.
- 2) Improve speed or frequency response ( $1/L$ ).
- 3) Improve current drive (Transconductance  $G_m$ ).
- 4) Decrease Power consumption

# TYPES OF SCALING

## 1) Constant Field Scaling or Full Scaling:

In this, all the parameter of the MOSFET is scaled to understand it in a better way we will consider a case, suppose the scaling factor is "S" who's values greater than 1 ( $S > 1$ ) now consider all the parameters of MOSFET is scaled by scaling factor "S" then it's all parameter will get changed to a new value. For example, if the original gate length is "L" then after scaling it will become  $L' = L/S$

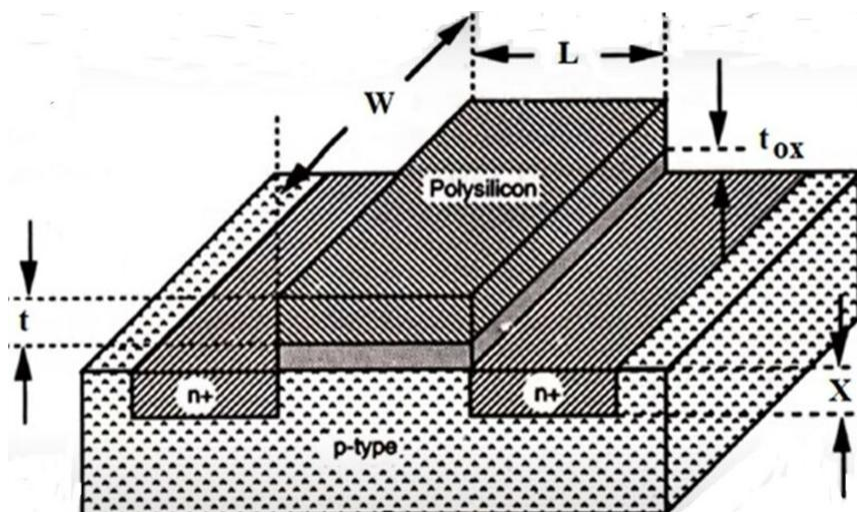
In a similar way, all parameters of the MOSFET will get changed to their new value hence this type of scaling is known as the Full Scaling.

## 2) Constant Voltage Scaling:

In this only, the physical parameters of the [MOSFET](#) are Scaled-down such as the Gate length of the MOSFET is decreased, and this result In a **Short Channel Effect** which will directly affect the Drain Current, therefore the drain [Current](#) is Inversely proportional to gate length. And electrical Parameters are kept constant, such as the terminal voltage of the MOSFET is kept constant.

## 3) Lateral Scaling:

In this type of scaling only the width of the gate channel is scaled. It's commonly called a **gate shrink**. This type of scaling is used only in specific applications. the disadvantage associate with this type is the high electric field through the channel and hence it also causes a **short channel effect**.



PARAMETER	BEFORE SCALING	AFTER SCALING	
		FULL SCALING	VOLTAGE CONSTANT SCALING
Channel length	$L$	$L' = L/s$	$L' = L/s$
Channel width	$W$	$W' = W/s$	$W' = W/s$
Gate oxide thickness	$t_{ox}$	$t_{ox}' = t_{ox}/s$	$t_{ox}' = t_{ox}/s$
Junction depth	$X_j$	$X_j' = X_j/s$	$X_j' = X_j/s$
Power supply voltage	$V_{DD}$	$V_{DD}' = V_{DD}/s$	$V_{DD}' = V_{DD}$
Threshold voltage	$V_{TO}$	$V_{TO}' = V_{TO}/s$	$V_{TO}' = V_{TO}$
Doping density	$N_A, N_D$	$N_A', N_D' = sN_A, sN_D$	$N_A', N_D' = s^2N_A, s^2N_D$
Oxide capacitance	$C_{ox}$	$C_{ox}' = C_{ox}/s$	$C_{ox}' = C_{ox}/S$
Drain current	$I_D$	$I_D' = s.I_D$	$I_D' = s.I_D$
Power dissipation	$P_D$	$P_D' = P_D/s^2$	$P_D' = S.P_D$
Power density	$P_D/\text{Area}$	$P_D/\text{Area}' = P_D/\text{Area}$	$P_D/\text{Area}' = s^3.P_D/\text{Area}$

# HISTORY OF CMOS

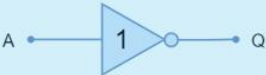


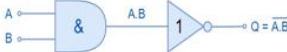

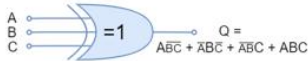
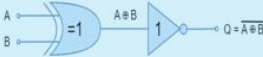
- ✓ 1963: Invention by Frank Wanlass at Fairchild Semiconductor.
- ✓ 1970s: Commercial adoption for low-power devices.
- ✓ 1980s: Dominance in microprocessors and memory.
- ✓ 1990s: Key to the rise of personal computing.
- ✓ 2000s: Central to the mobile device revolution.
- ✓ 2010s: Advanced techniques like FinFETs and high-k/metal gates.
- ✓ 2020s: Innovations in materials, 3D integration, and quantum computing.

# WORKING OF CMOS

- CMOS works on the **principle** of:

CMOS operates using **complementary pairs** of MOSFETs for low-power, noise-immune digital logic.

- In CMOS logic gates a collection of n-type MOSFETs is arranged in a **pull-down network** between the output and the low voltage ( $V_{ss}$  or ground).
- Instead of the load resistor of NMOS logic gates, CMOS logic gates have a collection of p-type MOSFETs in a **pull-up network** between the output and the higher-voltage ( $V_{dd}$ ).
- Furthermore, for better understanding of CMOS working principle, we need to discuss various logic gates (which discuss below).

NAME	SYMBOL	BOOLEAN
NOT		$Y = \overline{a}$
AND		$Y = \underline{a.b}$
OR		$Y = \underline{a+b}$
NAND		$Y = \overline{(ab)}$
NOR		$Y = \overline{(a+b)}$
XOR		$Y = (a \oplus b)$
XNOR		$Y = \overline{(a \oplus b)}$



# CMOS STRUCTURE OF INVERTER

## **NMOS Transistor** (Pull-down Network):

1. The NMOS transistor is connected between the output and ground.
2. When the input is high (logic 1), the NMOS transistor conducts, providing a path to ground and pulling the output low (logic 0).

## **PMOS Transistor** (Pull-up Network):

1. The PMOS transistor is connected between the output and the supply voltage ( $V_{dd}$ ).
2. When the input is low (logic 0), the PMOS transistor conducts, providing a path to  $V_{dd}$  and pulling the output high (logic 1).

# Fin-FET

- ❖ It is Type of **Multi Gate** MOSFET.
- ❖ It is widely use over **planar CMOS FET**.
- ❖ Fin is the channel in between **Source** and **Drain**.
- ❖ FinFET can have two or four or more Fin in same structure.
- ❖ It gives following advantages over FET
  - ☐ Area of performance
  - ☐ Lower Power Leakage
  - ☐ Low Voltage operation
  - ☐ Low Retention Voltage for SRAM
  - ☐ Better control over Current

